
METALIZATION – PLATING AND OTHER



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Metal Contact Deposition Techniques

Printing Metal Pastes

- Today's dominating technology for solar cell metallization
 - Feasibility for large scale production proven
 - Technological advances due to world-wide R&D activities
- Common high temperature approach requires glass frit for liquid phase sintering and adhesion on substrate
 - Glass layer partly covers contact area → high contact resistance
 - Glass frit usually contains Pb → Pb should be banned
- Low temperature approach for Hetero requires organic binder
 - Low conductivity → increased silver consumption
- **Silver is difficult to replace for low and high temp. approach because of its very special properties**

Metal Contact Deposition Techniques

Physical Vapor Deposition (PVD)

- Allows use of cheap materials (Ti, Al)
- Applied in micro electronics or optical disk manufacturing
- In-situ contact/silicide formation promoted by high particle energy
 - Excellent contact resistance
 - Good adhesion if chemical bonds are formed
- Extra patterning steps for grid definition on front-side necessary
- High invest and maintenance costs?

→ **Mainly interesting for rear side metallization**

Metal Contact Deposition Techniques

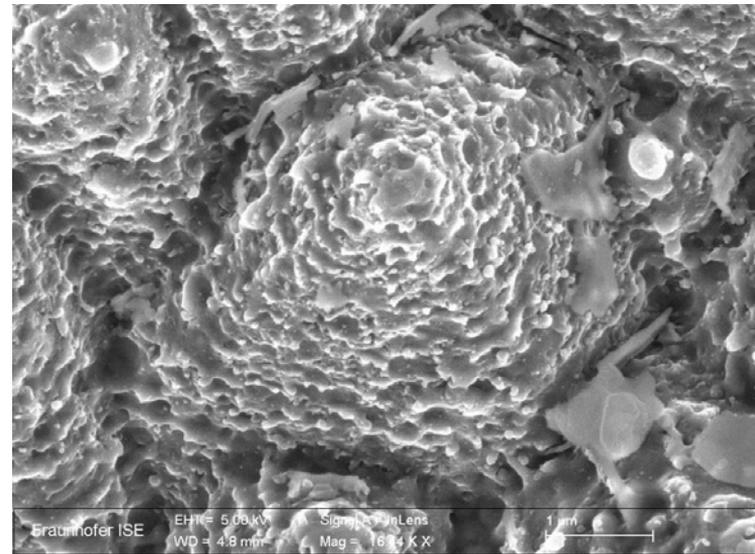
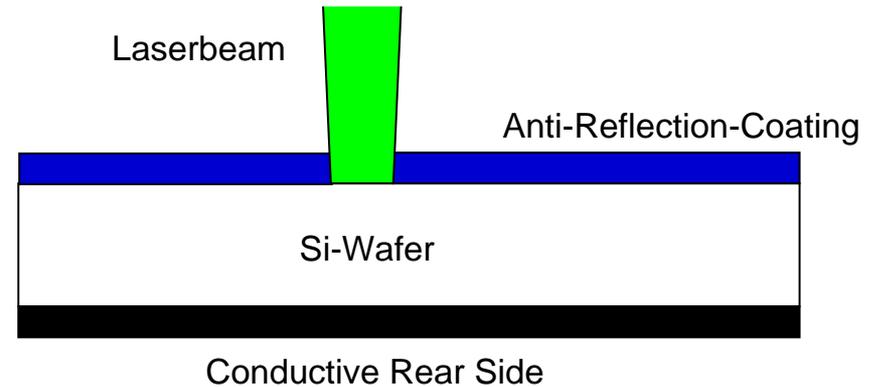
Plated Contacts

- Allows use of cheap materials (Ni, Cu, Sn)
- Low contact resistance can be reached (similar to PVD)
- But low deposition energy can hinder chemical bonding and electrical contact formation through native oxide
- Patterning steps for grid definition necessary
- Conductive layer necessary for electro-plating to spread electrical current

Plated Contacts for Al-BSF or PERC Solar Cells

Patterning

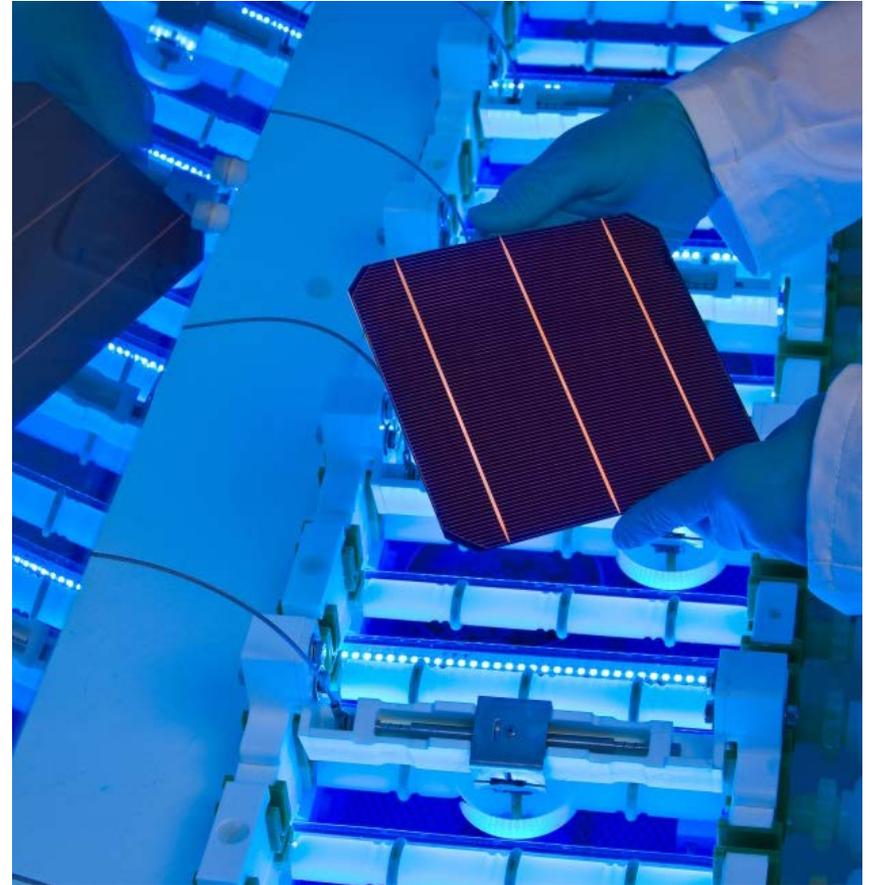
- Laser-patterned dielectric used as deposition mask
- At present UV ps-pulsed laser gives best results concerning adhesion



Plated Contacts for Al-BSF or PERC Solar Cells

Plating

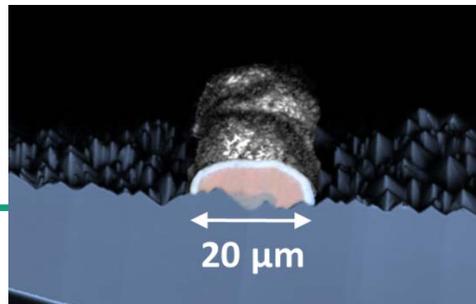
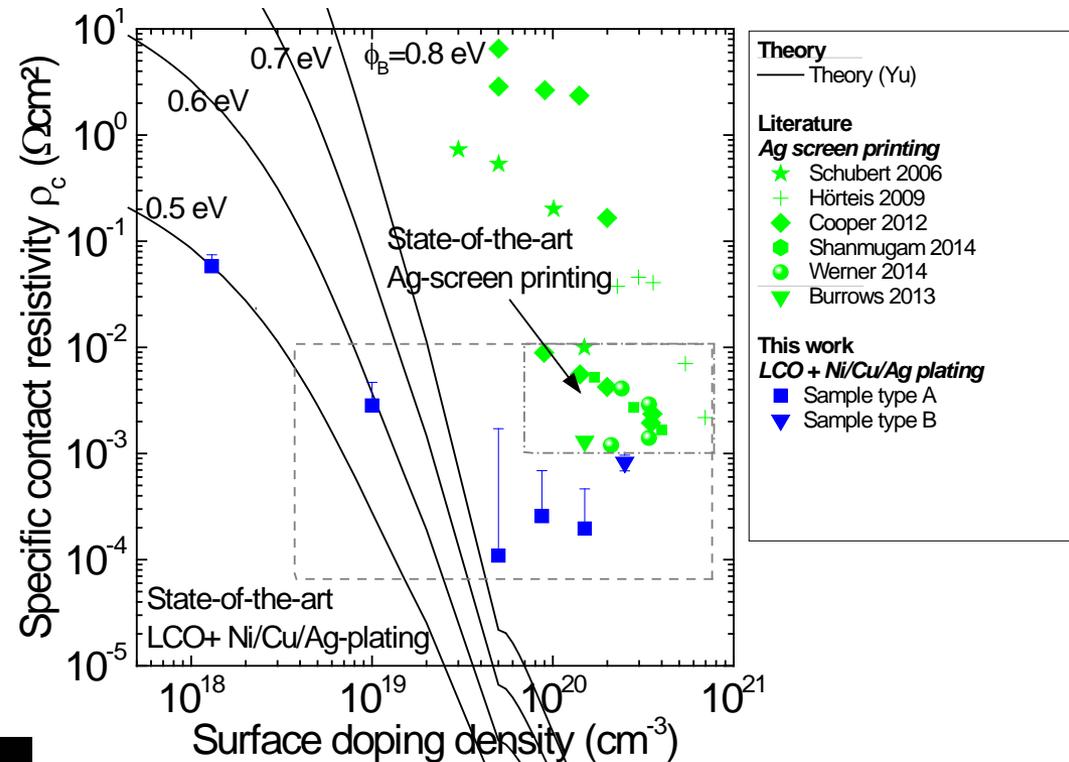
- Printed rear side used to spread current
- Light-induced plating
- Inline-tool similar to RENA-production tool
- Nickel seed layer as diffusion barrier
- Copper layer for lateral conductivity
- Silver capping layer to protect Cu from oxidation



Plated Contacts for Al-BSF or PERC Solar Cells

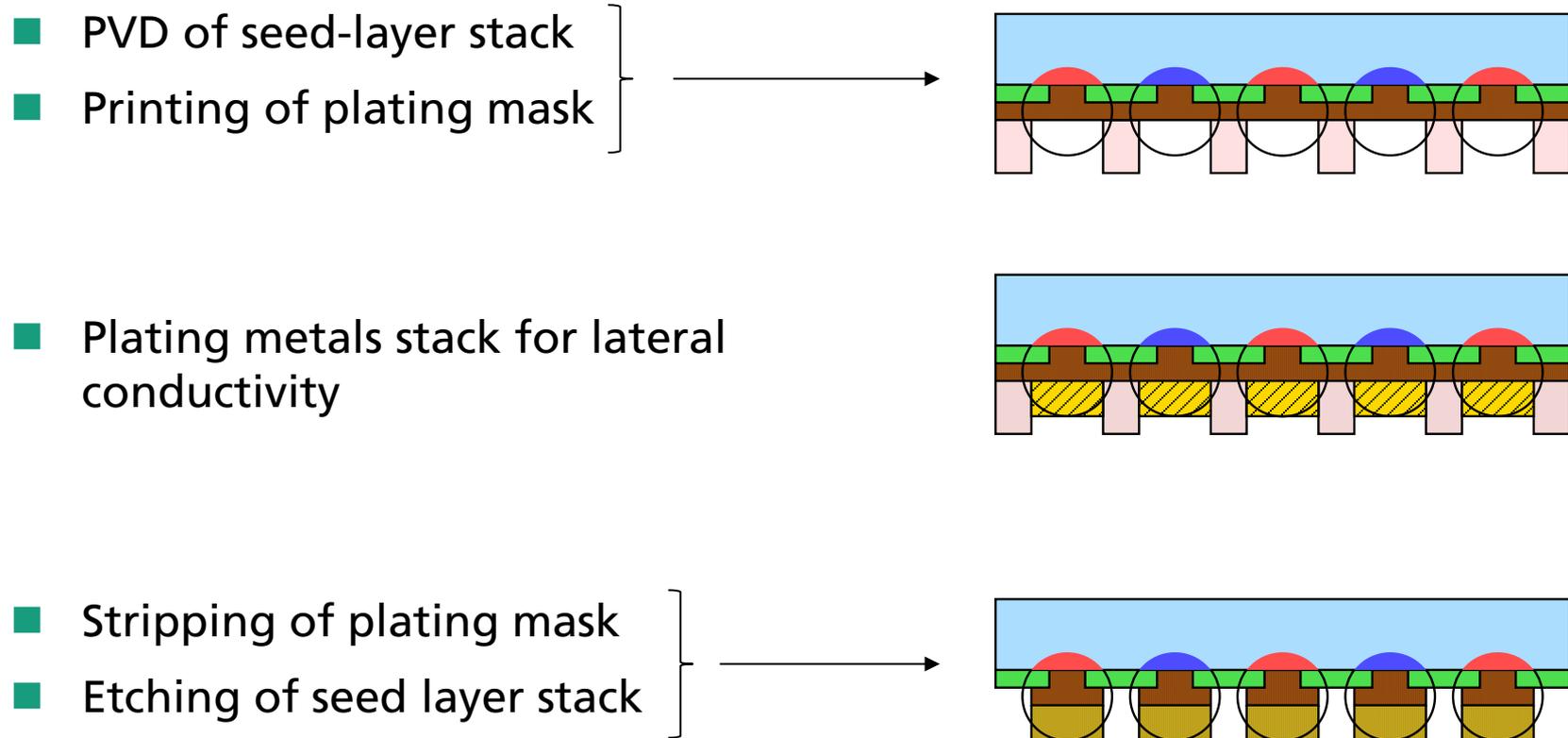
Results

- Finger width down to 20 μm demonstrated
- Excellent contact resistance for lightly doped emitters
- Sufficient adhesion and long term stability to pass related IEC-Tests
- Suitable for next generation PERC with $\eta > 22\%$



Plated Contacts for IBC Solar Cells

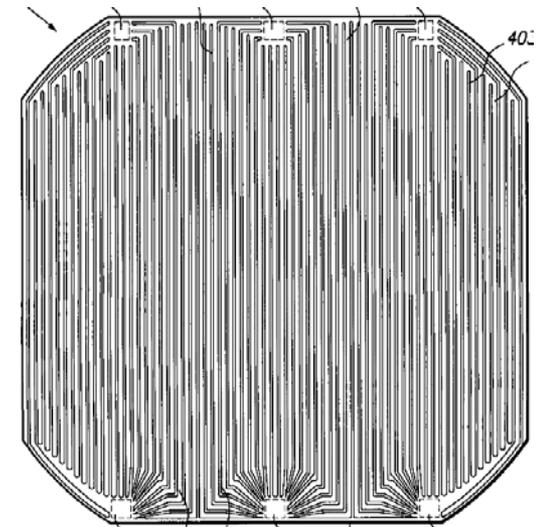
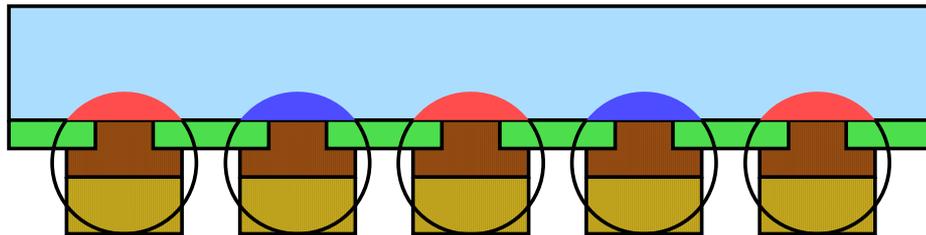
Standard Process Flow



Plated Contacts for IBC Solar Cells

Standard Process Flow

- Process applied in mass production (~ 1 GW/a by SunPower)
- Lead free, no or low Ag consumption
- Excellent contact properties with PVD Al
- But rather expensive process steps



Sketch from De Ceuster Patent, 2010

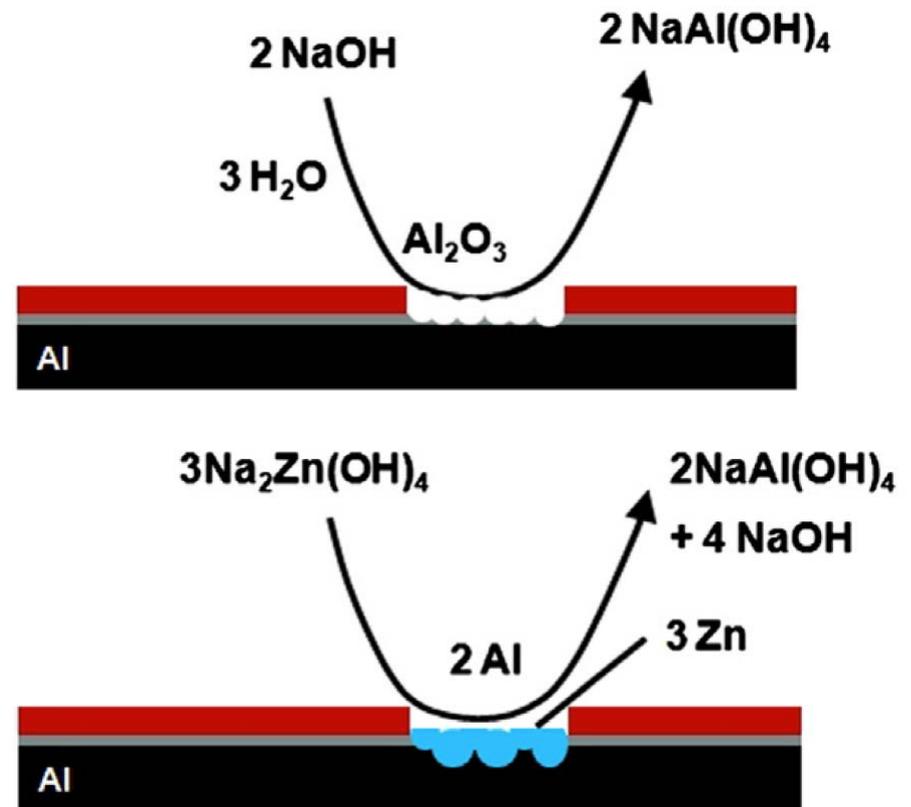
Plated Contacts for IBC Solar Cells

Zincate Process

- Cost for PVD-layers higher than for wet-chemical deposition



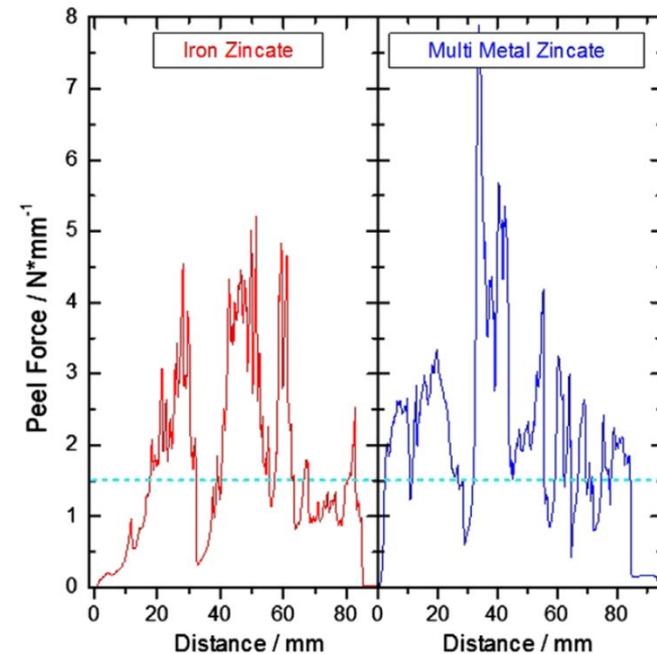
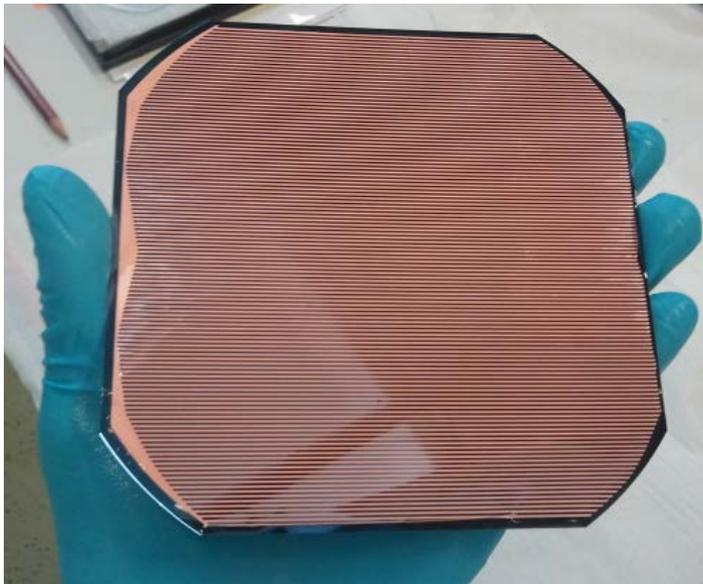
- PVD of only Al seed layer
- Chemical conditioning for plating via zincate process
 - NaOH etches native Oxide
 - Al-Atoms replaced by Zn-Atoms
- Plating of Ni, Cu and Sn with standard electrolytes



Plated Contacts for IBC Solar Cells

Zincate Process

- Process demonstrated on large area
- Peel force of up to 7 N/mm reached → exceeds requirements of IEC



Plated Contacts for IBC Solar Cells

Electrochemical Patterning

- Stripping of organic plating resist causes high costs for waste-water treatment

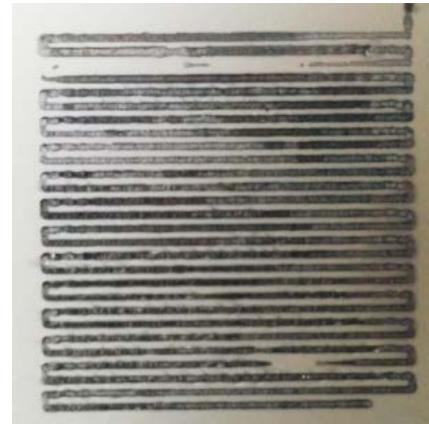
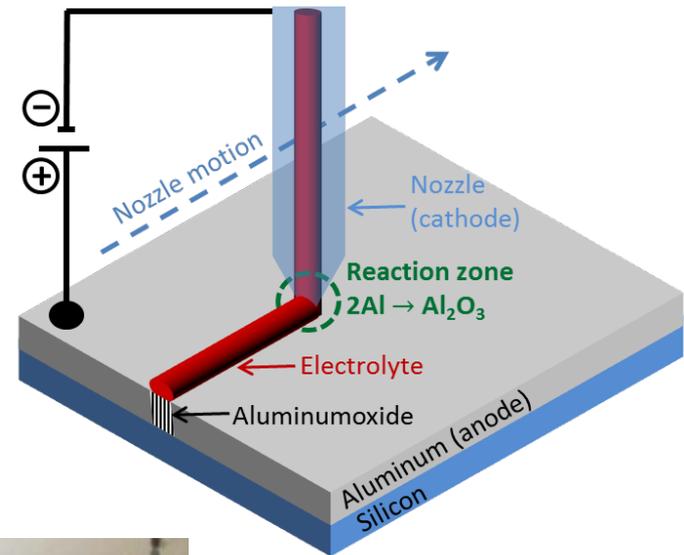


- Electrochemical patterning of Al-surface by local anodization

Plated Contacts for IBC Solar Cells

Electrochemical Patterning

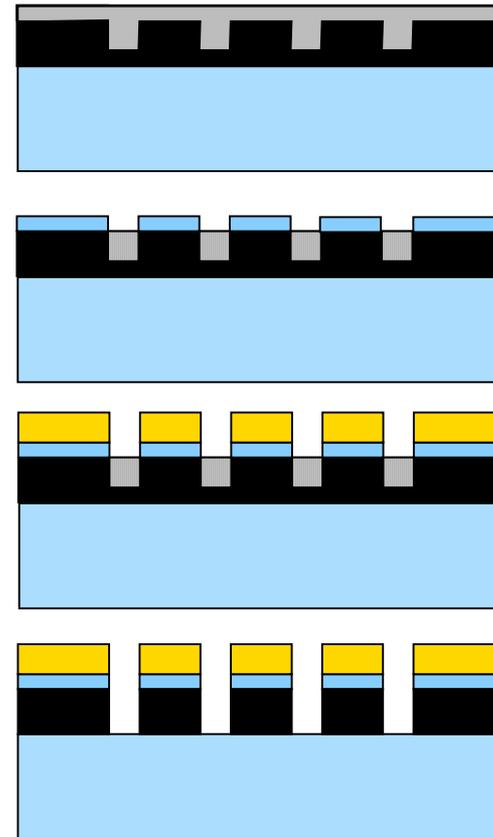
- Dispensing system for patterning
 - Adapted electrolyte as ink
 - Voltage applied between nozzle and substrate
- Thick Al_2O_3 -layer is formed, that is not removed in zincate process



Plated Contacts for IBC Solar Cells

Simplified Metallization Process

- Electrochemical patterning of Al-layer
- Surface treatment with zincate process
- Plating for lateral conductivity
- Etching of residual Al for contact separation



Plated Contacts for Silicon Hetero-Junction Solar Cells

Negative Masking

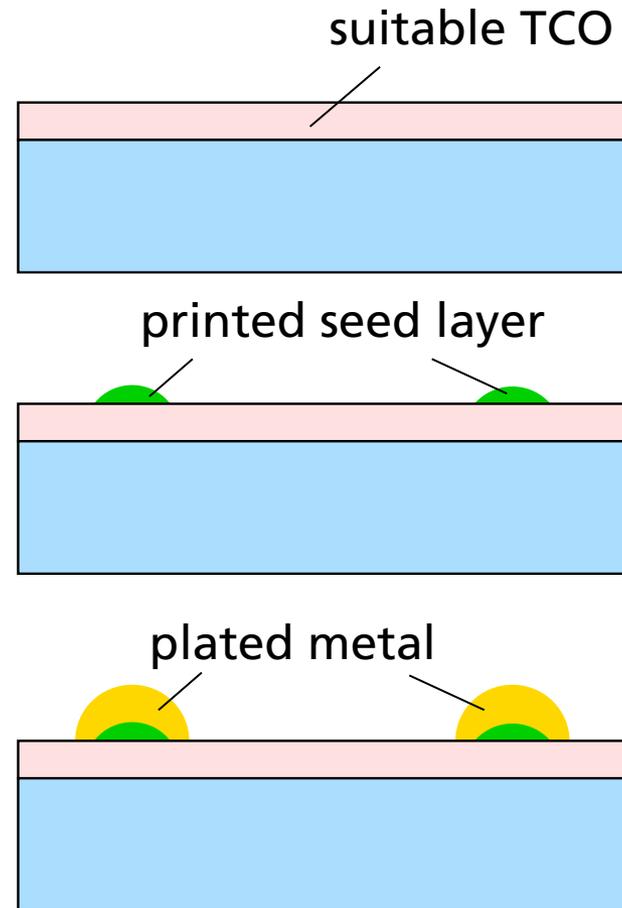
- ITO is a good diffusion barrier for Cu
- Ni and Cu plate on ITO

- Patterning techniques for grid deposition by applying negative mask
 - Photo lithography (CSEM)
 - Inkjet-printed resist (OTB)
 - Laser patterned resist (SERIS/ISE)
 - ...
- Silevo/SolarCity claims to start mass production (1 GW/a) with such process
- Concerns about costs!

Plated Contacts for Silicon Hetero-Junction Solar Cells

Positive Masking

- No plating on certain TCOs or or even metals observed
- Theses TCOs or metals can be electrically contacted by printed seed layer
- Grid can be defined by printed seed layer on suitable TCO layer



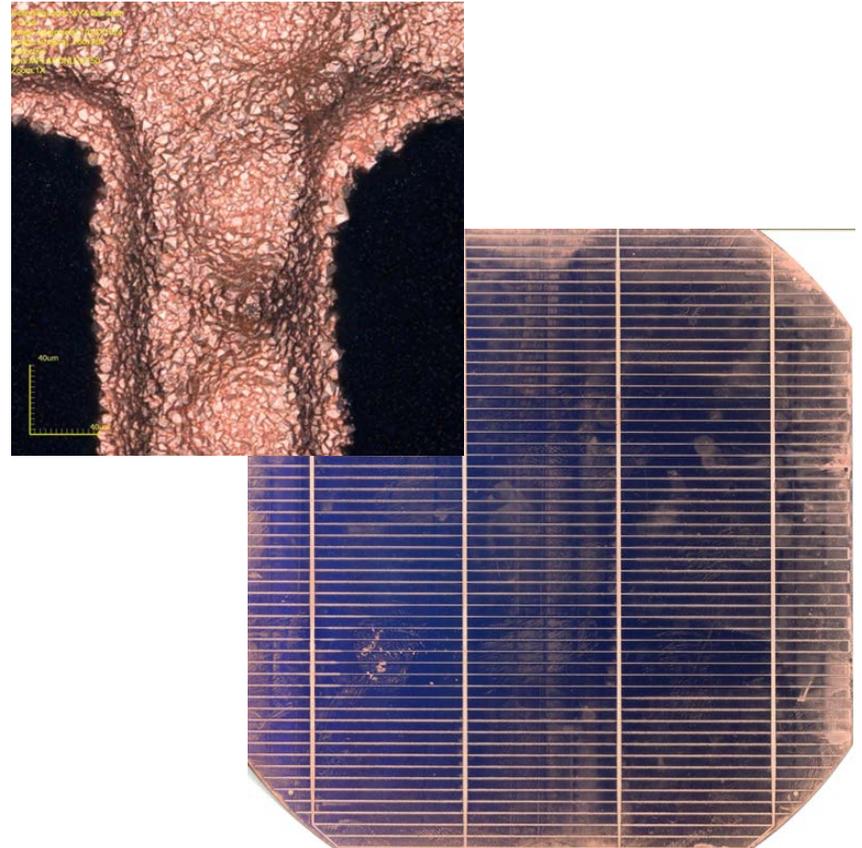
Plated Contacts for Silicon Hetero-Junction Solar Cells

Positive Masking

- Proof of principle given on standard ITO with printed silver seed layer (CSEM solar cells)

ToDo:

- Mechanism for selectivity of plating process need to be investigated
 - Avoid parasitic plating
 - Increase plating speed
- Tailor ITO properties
- Use of different TCOs
- Check edge isolation



Conclusion

- Plating on Al-BSF or PERC solar cells mature to start integration into production
- Plated front side highly promising for next generation PERC with >22% without use of Ag or Pb
- Plating already applied in industrial IBC solar cell production
- Cost reduction potential by simplified process sequence
- Plating on silicon hetero-junction solar cells very interesting
- Best masking technology not identified yet